

Appendix-1

| Description | | LN 2 Plant (Optional) | | Main facility | | | | | | | | | | | | | |
|--------------------------------|-------|------------------------|----------------|----------------|----------------|-------------------------|-----------|-----------|-----------|-----------|-----------|-----------|-----------|-----------|--------------|---------------|-----|
| | | General Purity | High Purity | General Purity | High Purity | Trickle purge from GPN2 | | | | | | | | | | | |
| | | N2 (99.999 %) | N2 (99.999 9%) | N2 (99.999 %) | N2 (99.9999 %) | N2 (99.999%) | Ar | O2 | H2 | He | C4F8 | SF6 | N2O | SiH4 | 1% PH3 in H2 | 1% B2H6 in H2 | NH3 |
| POCs | SI no | Facility | | | | | | | | | | | | | | | |
| | 1 | NIL-UV | | 1 | | 1 | | | | | | | | | | | |
| | 2 | NIL-HE | | 1 | | 1 | | | | | | | | | | | |
| | 3 | Bake module | | | | | | | | | | | | | | | |
| | 4 | Mask aligner | | 1 | | 1 | | | | | | | | | | | |
| | 5 | Electroplating | | 1 | | 1 | | | | | | | | | | | |
| | 6 | WB-1 | | 1 | | 1 | | | | | | | | | | | |
| | 7 | WB-2 | | 1 | | 1 | | | | | | | | | | | |
| | 8 | WB-3 | | 1 | | 1 | | | | | | | | | | | |
| | 9 | WB-4 | | 1 | | 1 | | | | | | | | | | | |
| | 10 | Coater and developer | | 1 | | 1 | | | | | | | | | | | |
| | 11 | Wire bonder | | 1 | | 1 | | | | | | | | | | | |
| | 12 | EBW | | | | | | | | | | | | | | | |
| | 13 | Seam sealer | | 1 | | 1 | | | | | | | | | | | |
| | 14 | Wafer dicer | | | | | | | | | | | | | | | |
| | 15 | Wafer dicer - Cleaning | | | | | | | | | | | | | | | |
| | 16 | Wafer dicer - Mounting | | | | | | | | | | | | | | | |
| | 17 | CPD | | | | | | | | | | | | | | | |
| | 18 | E-beam evaporation | | 1 | | 1 | | | | | | | | | | | |
| | 19 | Plasma cleaner | | | | | | 1 | 1 | | | | | | | | |
| | 20 | Wafer bonder | | 1 | | 1 | | 1 | 1 | | | | | | | | |
| | 21 | He bombing chamber | | | | | | | | 1 | | | | | | | |
| | 22 | FCB | | 1 | 1 | 1 | 1 | | | | | | | | | | |
| | 23 | DRIE | | 1 | | 1 | | 1 | 1 | 1 | 1 | 1 | 1 | | | | |
| | 24 | PECVD | | 1 | 1 | 1 | 1 | 1 | 1 | 1 | | | 1 | 1 | 1 | 1 | 1 |
| Additional POC per LAB | | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | 1 | |
| Total POC's | | 17 | 3 | 17 | 3 | | 5 | 6 | 3 | 3 | 2 | 3 | 2 | 2 | 2 | 2 | |
| Total consumption (Nm3/month) | | 8933 | 962 | 8933 | 962 | | 18.5 | 160 | 141 | 110 | 16 | 30 | 3 | 1.5 | 1 | 1 | |
| MOC | | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | SS316L EP | |
| Distribution tubing type | | Single | Single | Single | Single | Single | Singl | Single | Singl | Singl | Single | Single | Single | Co Axial | Co | Co | |

| | | | | | | | | | | | | | | | | |
|-----------------------|-----------------|-----------------|--------------------|-------------------|-------------------|---------------------------|--------------------|---------------------------|---------------------------|-------------------|-------------------|-----------------|----------------|----------------|--------------------|----------------|
| | walled | walled | walled | walled | walled | e wall ed | walled | e wall ed | e wall ed | walled | walled | walled | | Axial | Axial | Axial |
| Flow Rate (sccm) | 1500 | 1000 | 500 | 1000 | NA | | 1000 | 1000 | 1300 | 600 | 1500 | | | | | |
| Header Pressure (Bar) | 10 | 10 | 10 | 10 | 10 | | 10 | 10 | 10 | 10 | 10 | | | | | |
| POU Pressure (Bar) | 0-8 | 0-8 | 0-8 | 0-8 | 0-8 | | 0-8 | 0-8 | 0-8 | 0-8 | 0-8 | | | | | |
| source | New Facility | New Facility | Existin g Panel | Existing Panel | Existing Panel | Exis ting Pane l | Existin g Panel | Exis ting Pane l | Exis ting Pane l | Existing Panel | Existing Panel | New Facility | Gas Cabinet | Gas Cabinet | Gas Cabin et | Gas Cabinet |